

IR Detector characterization at CEA LETI

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Agenda

1. II VI process line at LETI

2. Characterization means

3. Focus on some figures of merit

QE

Pixel PSF & MTF

Persistence

Irradiation testing

4. Conclusion





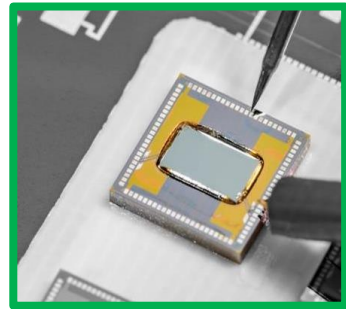
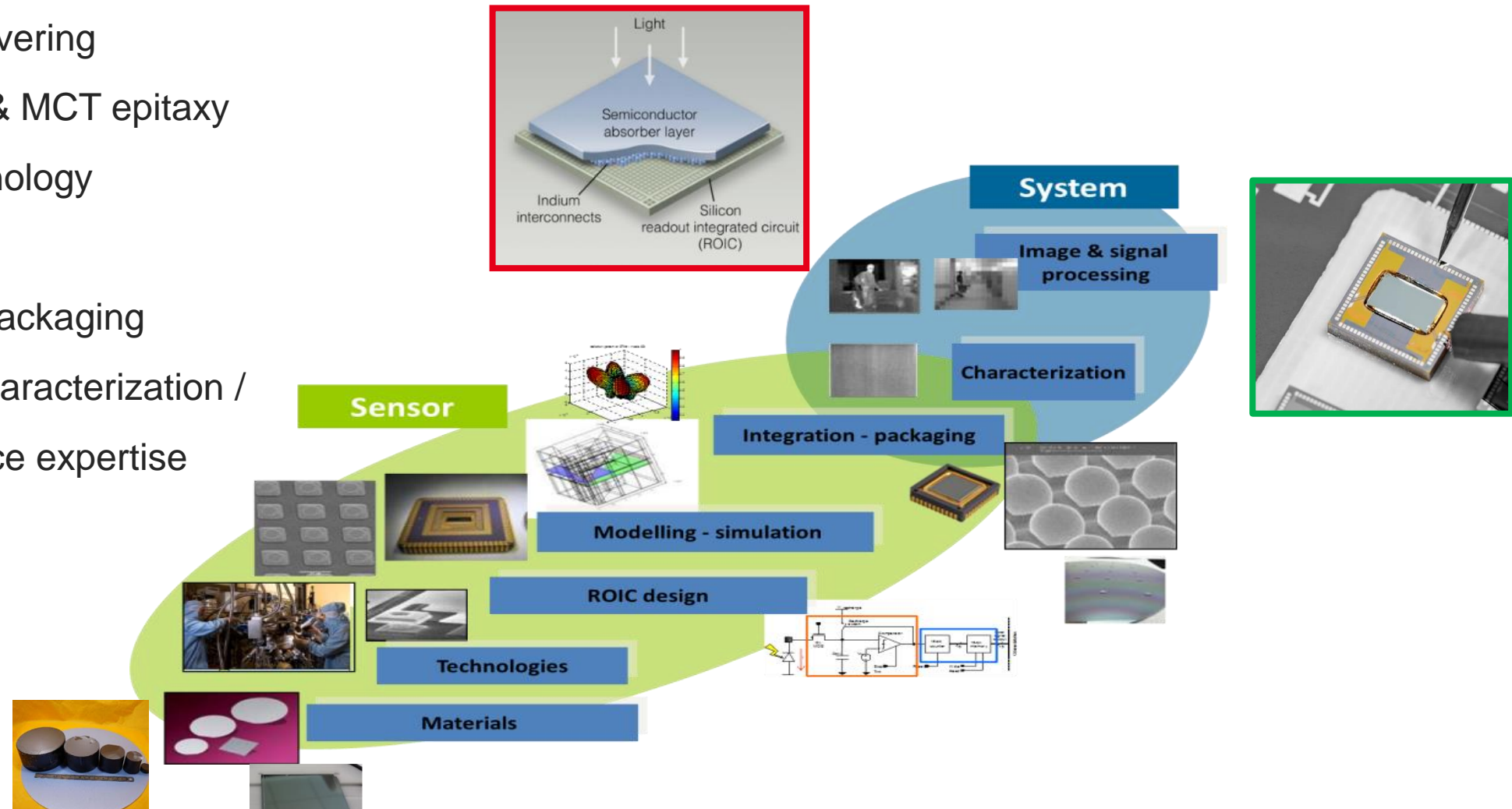
1. **II VI process line at LETI**

General presentation

What do we do: developing technologies for high performance **cooled IR imagers** and **APD**.

Full process flow covering

- Substrat growth & MCT epitaxy
- Photodiode technology
- ROIC design
- Hybridization & packaging
- Electro-optical characterization / simulation / device expertise

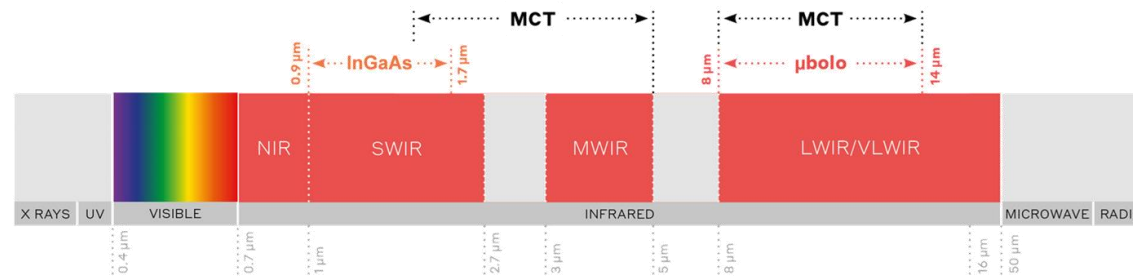


General presentation

A wide electro-optical characterization range covered:

- From material quality, photodiodes or test chips to full hybridized array
- ROIC types :
 - SFD, DI, CTIA, APD
 - Analog or digital

Spectral bands:



Applications:

- Defense
- Earth observation from space
- Science and astronomy
- Telecom FSO, LIDAR, quantum optics with mono-element APD

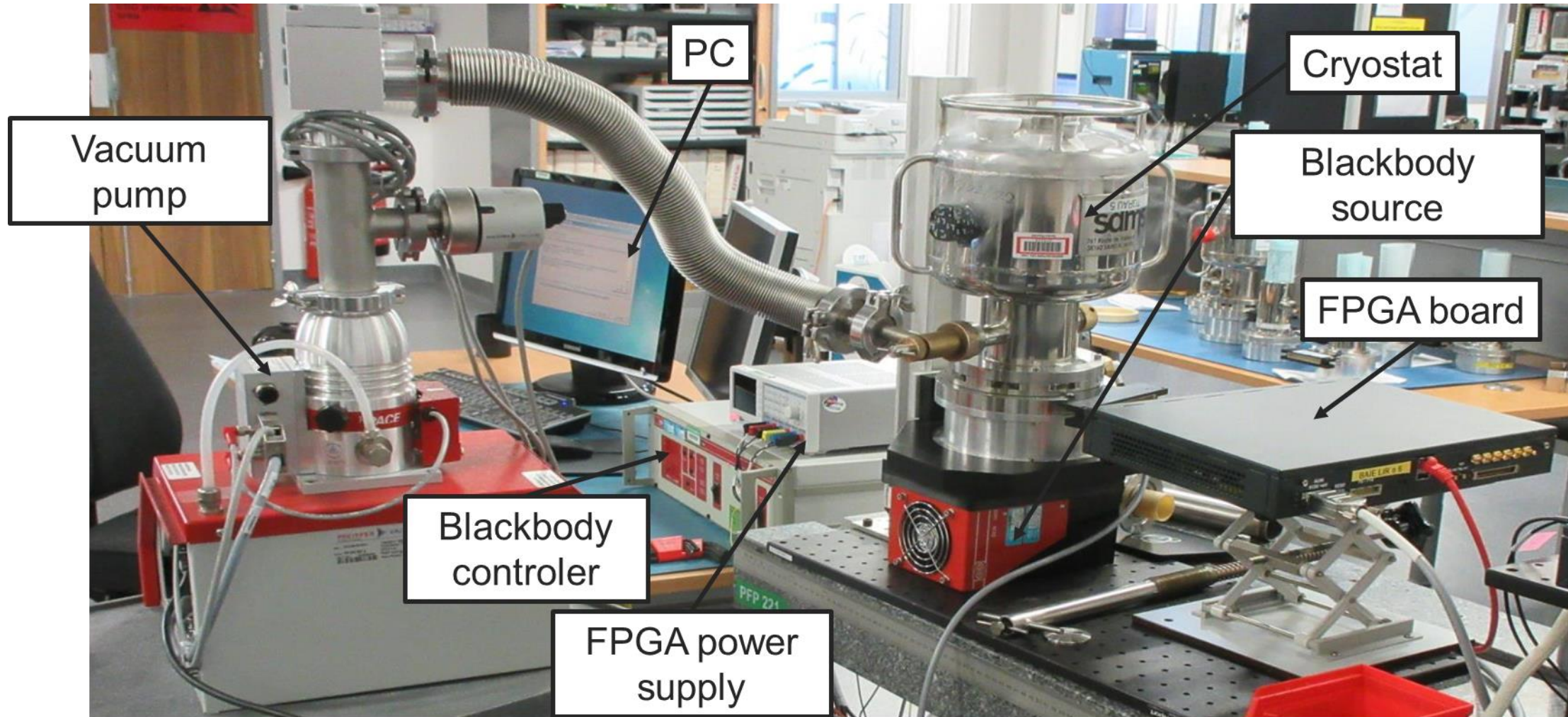


MONPHOTONICS



2. **Characterization means**

Characterization means

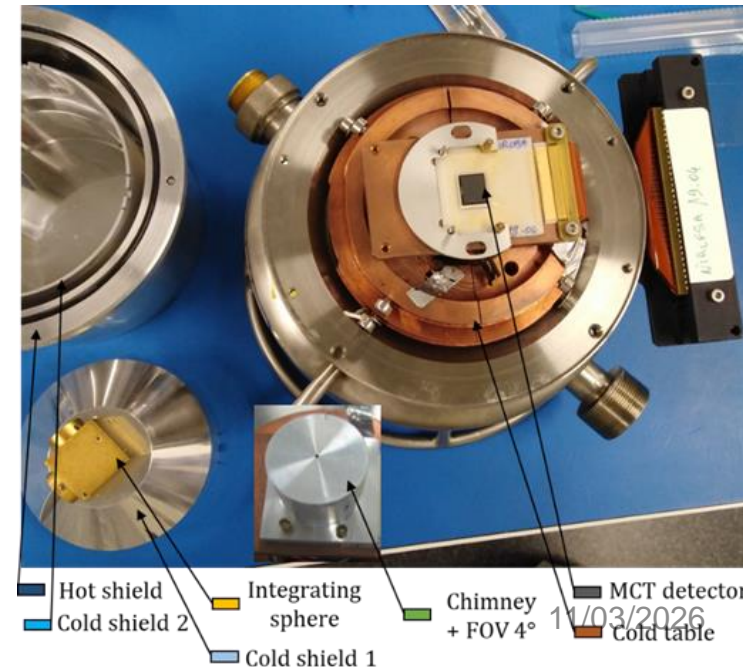
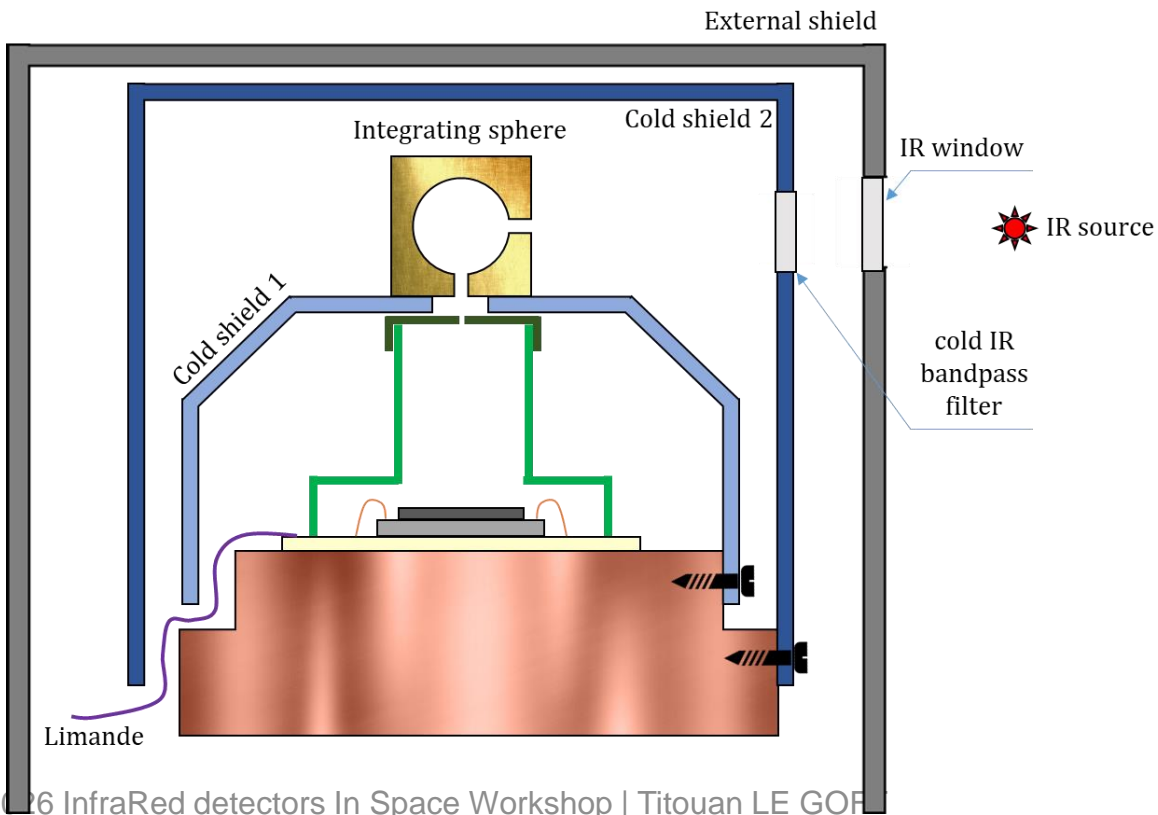


Fits in a car and can be transported at an irradiation facility for instance !

Characterization means

Liquid N_2 cooled Cryostat with integrating sphere

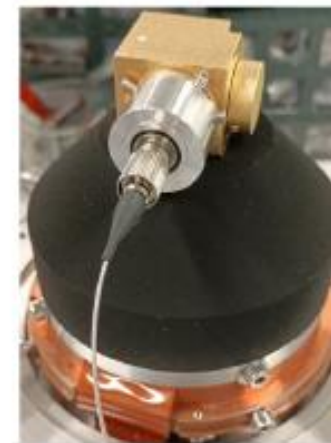
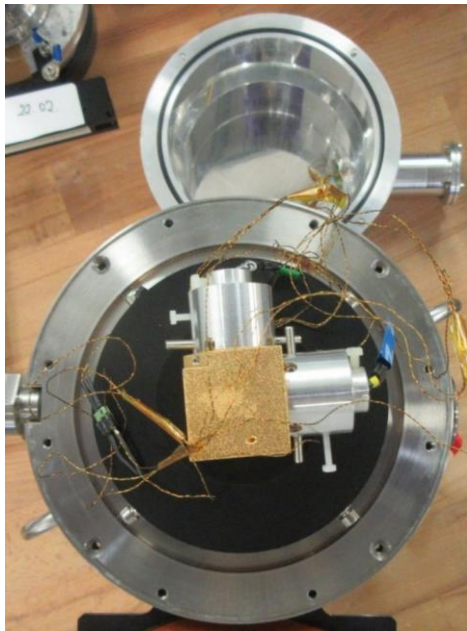
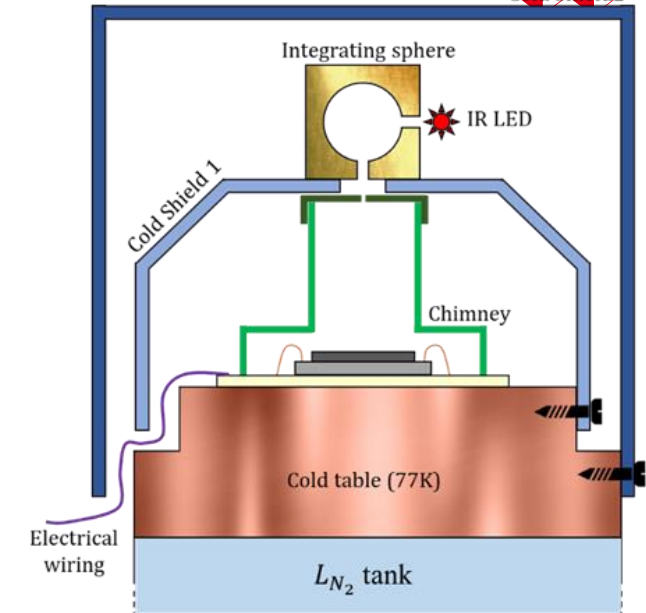
- Classical blackbody illumination
 - Hot output window
 - Optionnal cold bandpass filter
 - Cold integrating sphere



Characterization means

Liquid N_2 cooled Cryostat with integrating sphere

- LED configuration
 - Light leak < 0,001 ph/s
 - Pulsed mode : 4 $ph/pix/puls$
 - Continuous mode: > 100pA/pixel
- Optical fiber configuration
 - Degraded dark condition
 - Fibered LED or laser input
 - Blackbody illumination still possible





3. Focus on some figures of merit

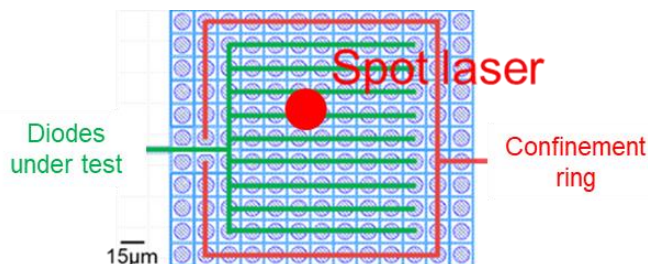


3 ■ 1 QE on test chip

QE on test chip

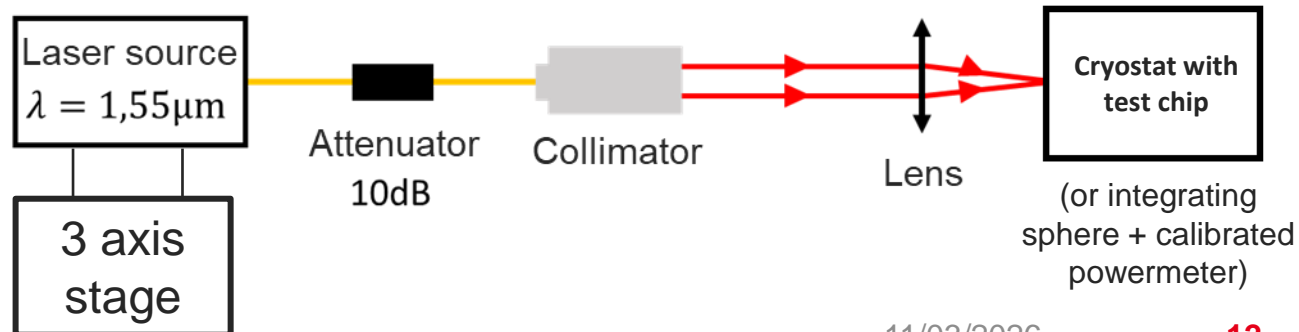
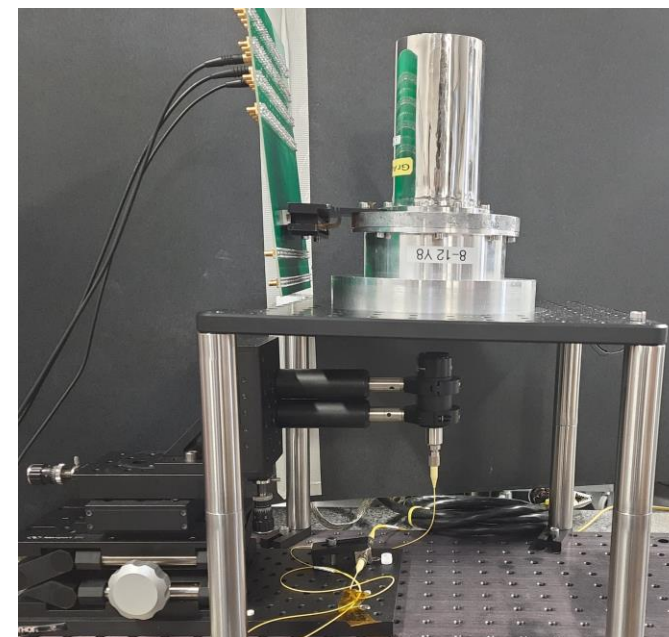
□ Principle:

- Focusing a laser (1.55 μm) spot
- Calibrating laser source with powermeter
- Test chip: **cluster of interconnected photodiodes**



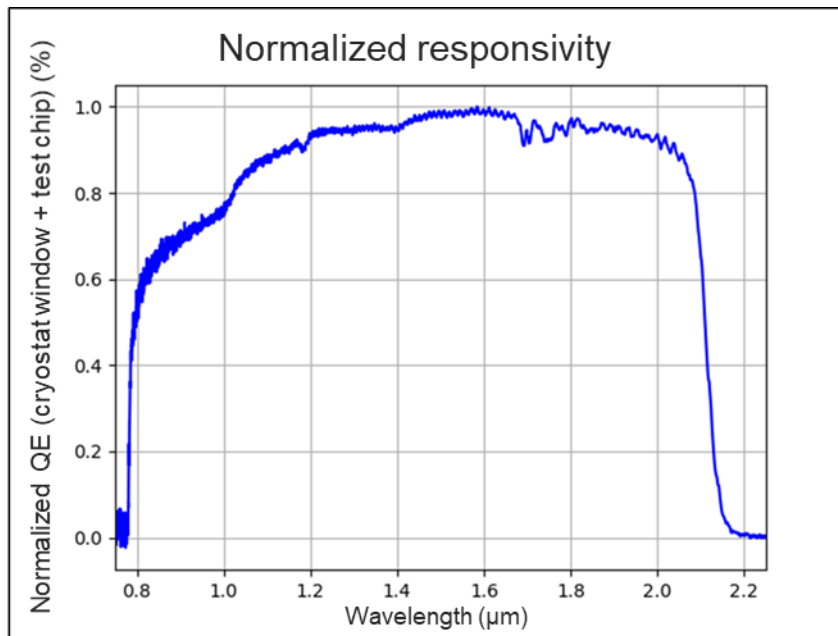
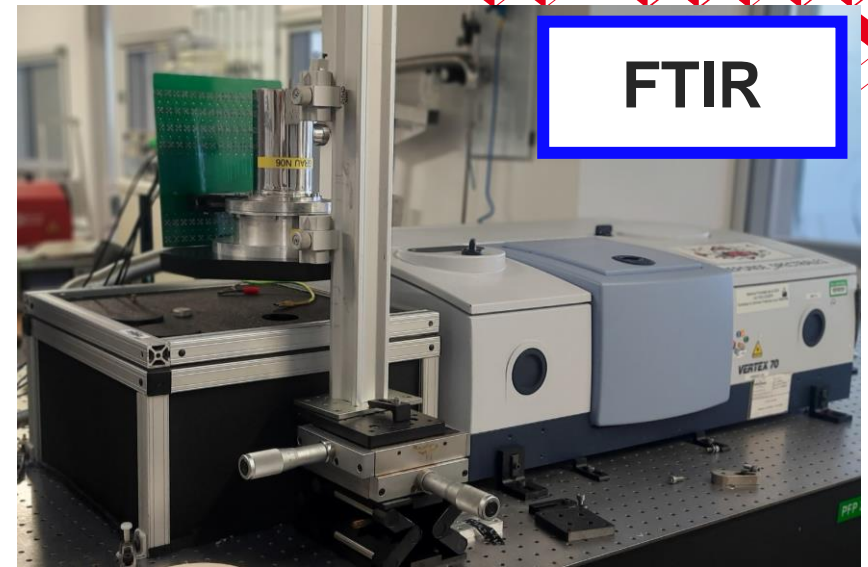
□ Challenges:

- Laser spot must be narrower than the diode cluster (theoretical $\Phi_{spot} < 10\mu\text{m}$)
- Collection surface must be known -> confinement ring
- The cluster must be homogenous
- Tolerance to small position variation

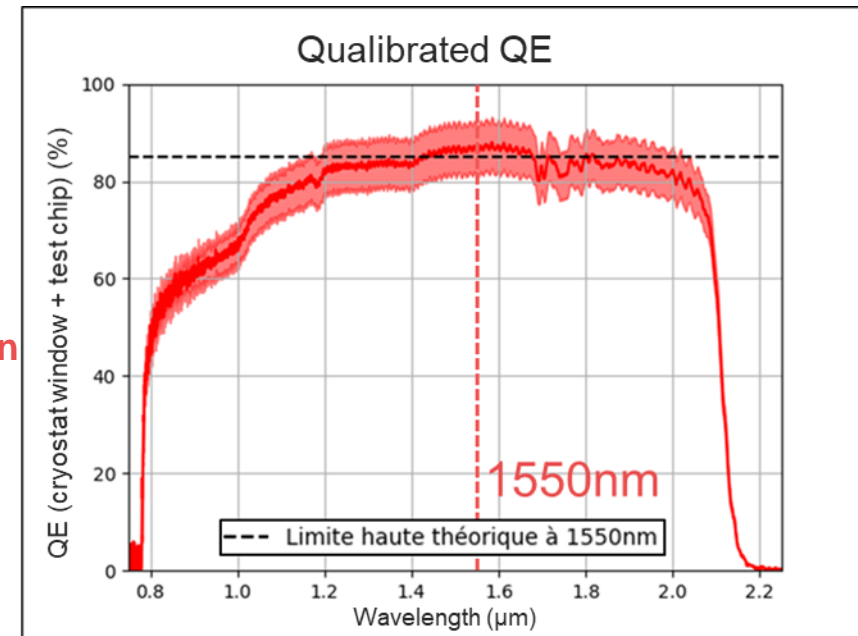


QE on test chip

- ❑ QE obtained : 85% at 1.55 μm (including cryostat window)
 - ALFA P/N technology (2.1 μm cutoff)
 - 9x9 or 6x6 15 μm pitch test chips
 - Independant on P_{laser}
 - ~6% total uncertainty
- ❑ Can be combined with normalized responsivity to get **spectral QE**



➔
QE calibration
(1550nm)

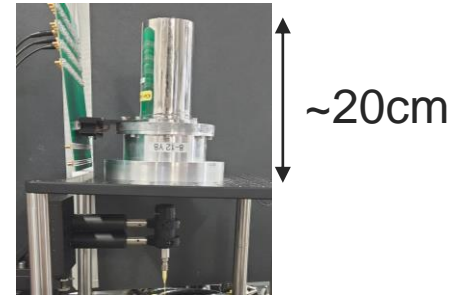
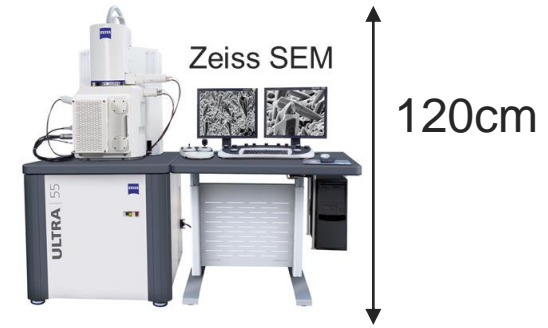




3 ■ 2 Pixel PSF & MTF

PSF characterization

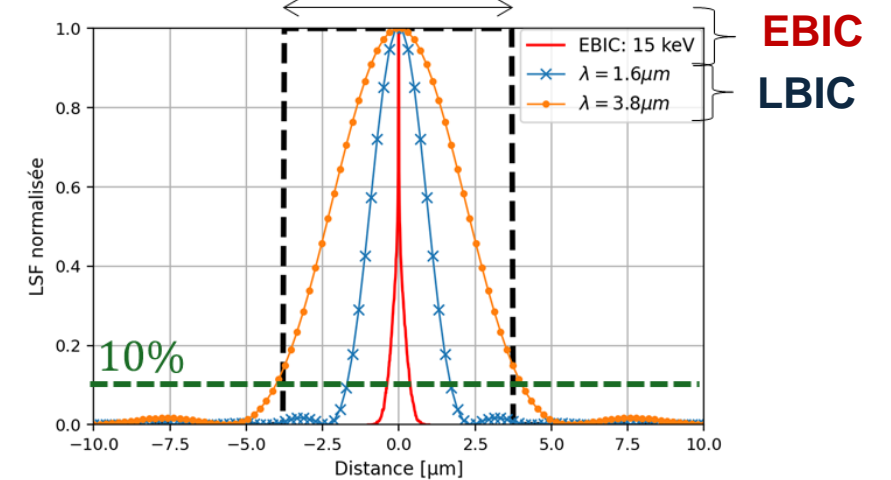
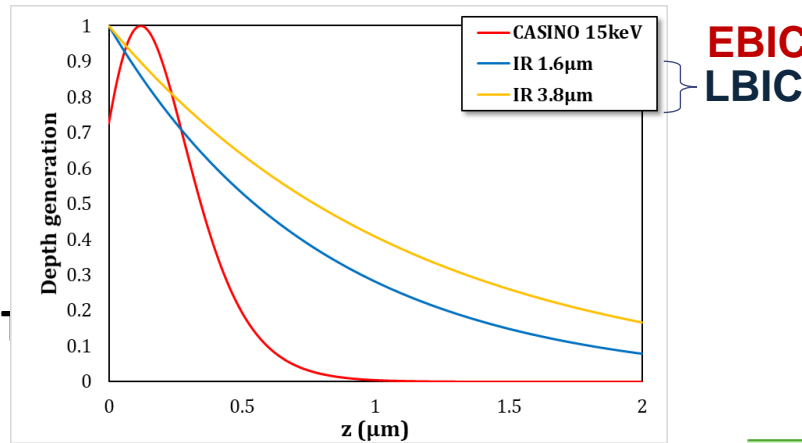
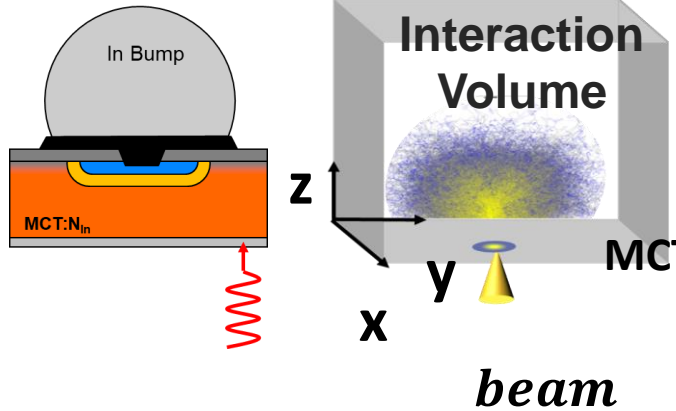
- Objective : MTF on **MWIR ($\lambda_c 5\mu m$)** & small pixel pitch [15 -> **5 μm**].
- 2 technics developed at LETI:
 - Laser beam induced current (LBIC) @1.55 μm
 - Electron beam induced current (EBIC)



Beam lateral extension

7.5 μm

Volume extension



Direct PSF measurement, no deconvolution

No substrate removal required

Volume generation of e⁻/h⁺ pairs

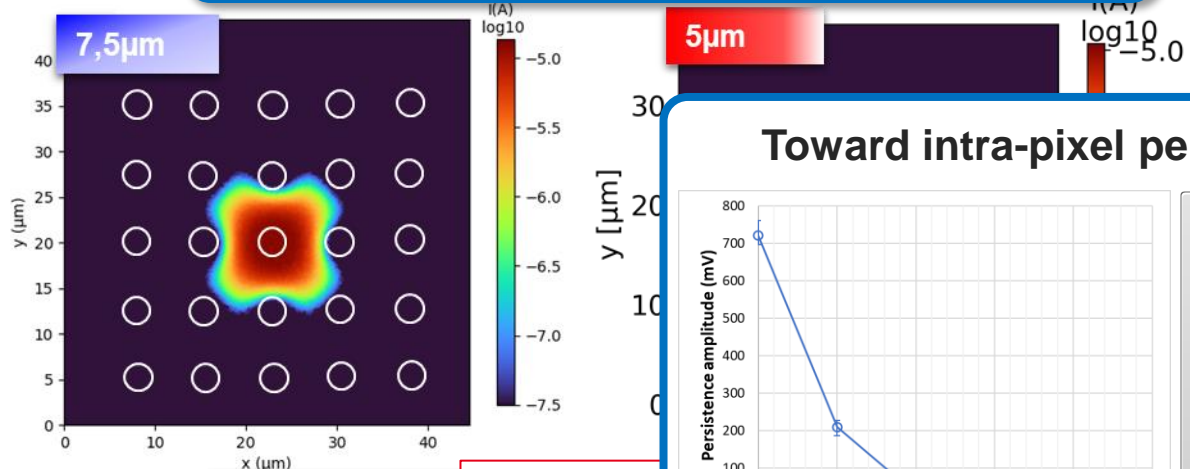
	$\Delta_{horizontal}^{10\%}$	MTF($f_{Ny} = 67$)
→ EBIC (15 keV)	0.75 μm	>99%
→ $\lambda = 1.6 \mu m$	3.5 μm	83%
→ $\lambda = 3.8 \mu m$	7.9 μm	61%

PSF with EBIC probe

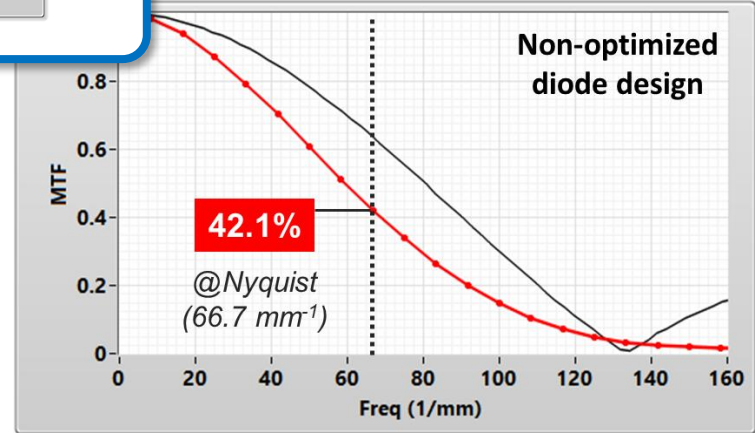
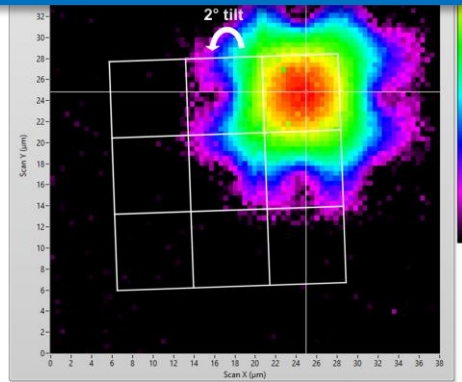
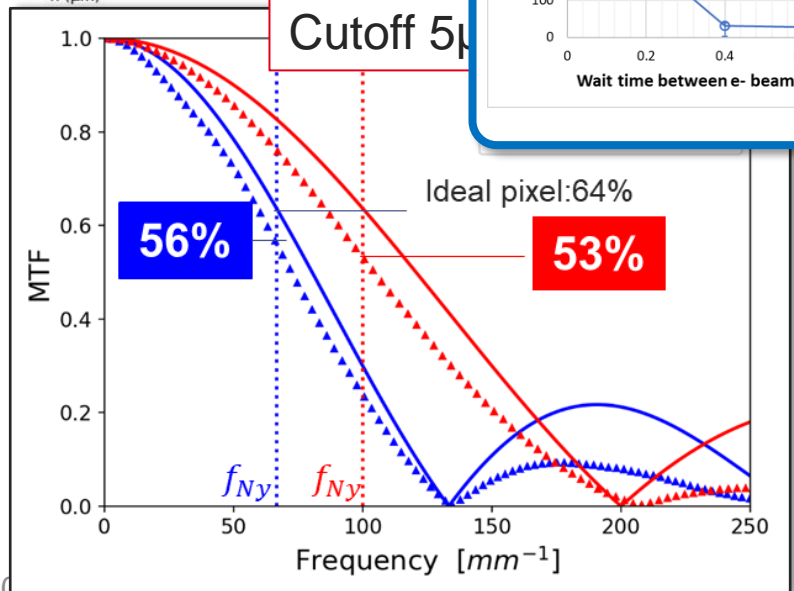
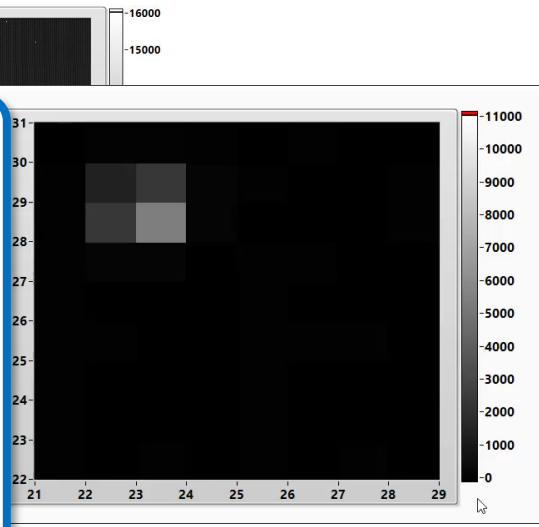


MWIR diodes in an array configuration
Backside charge injection

1024*1280 7.5μm pix MWIR FPA (direct injection)



Toward intra-pixel persistence mapping with EBIC ?



Pixel PSF

FFT

Pixel MFT



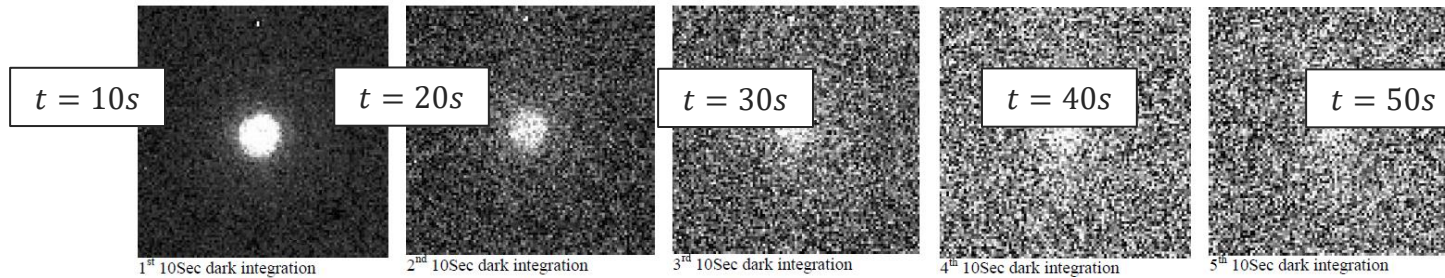


3 ■ 3 Persistence

Persistence definition

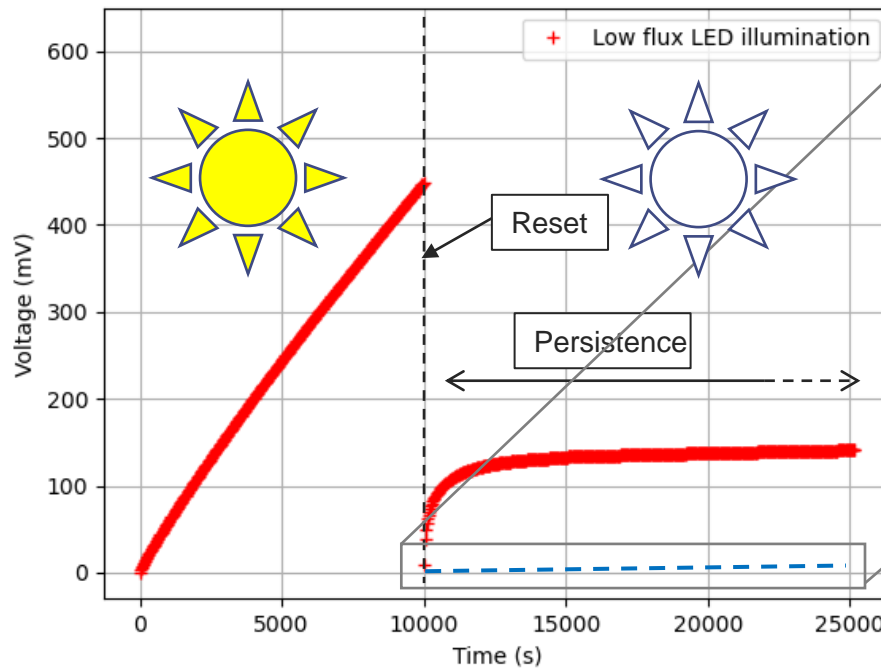
Persistence

= Transitory after any previous stimulation (photon flux, voltage change, particle impact ...)

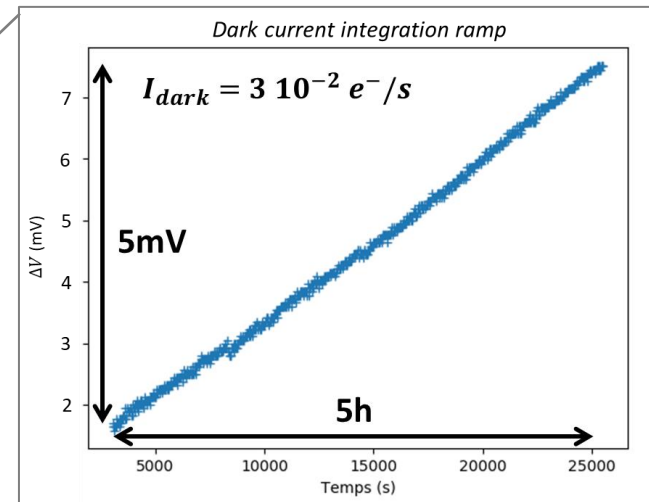


N. Besawada (2004)

Persistence : excessive and non-linear signal



Expected linear dark current



Persistence : How to measure it ?

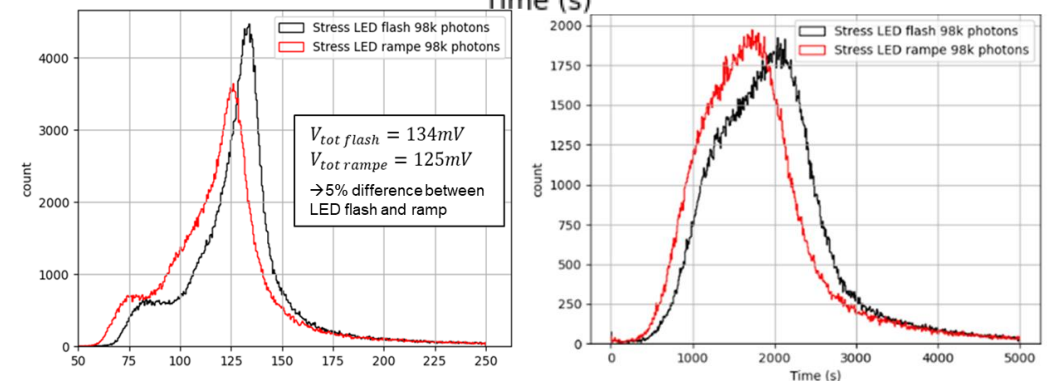
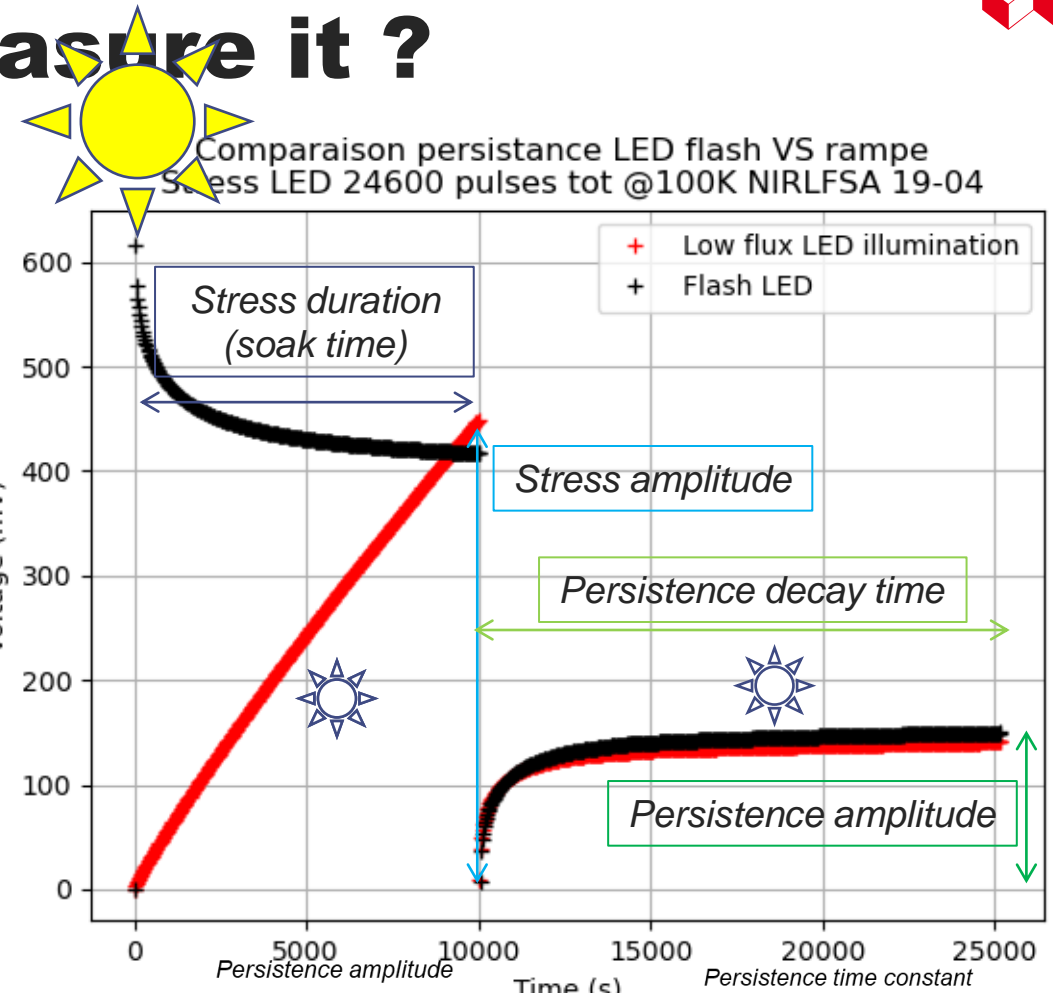
Type of measurement:

- Detector conditioning before any measurement
- Long and diffuse **illumination ramp**
- **Optical flash + soak time**
 - LED flash / ramp difference : **persistence also has impact on photometry !**

-> effect related to the charge time of persistence

Parameters of interest

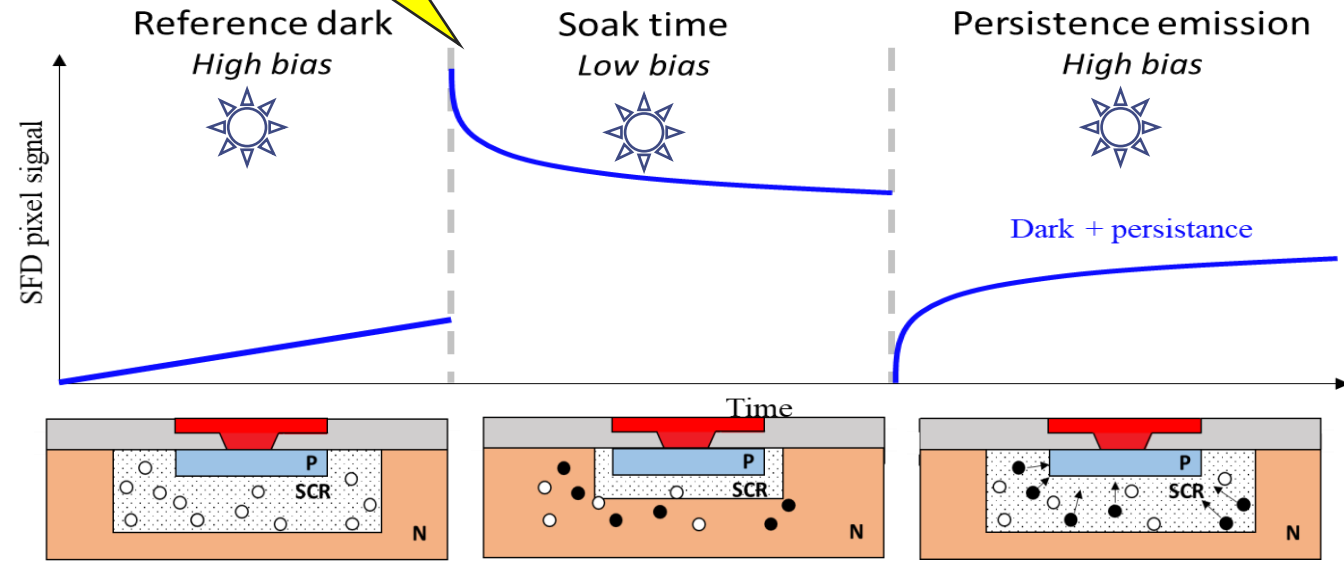
- Amplitude : photon fluence or ΔV
- Soak time
- Operating temperature



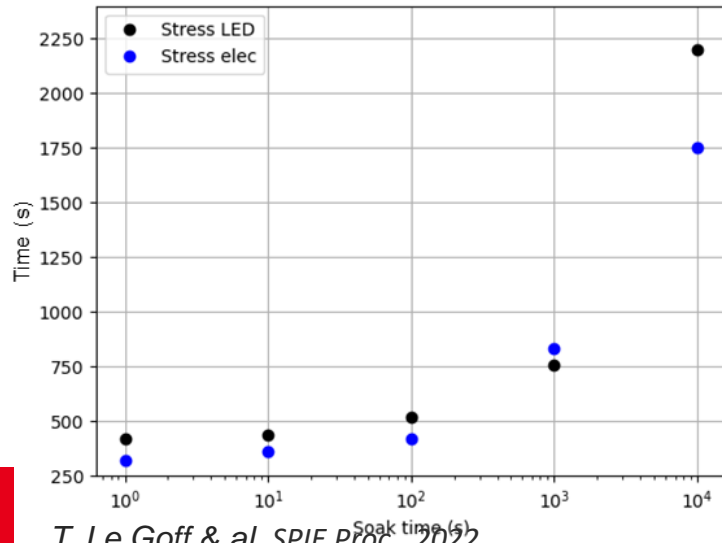
Persistence : How to measure it ?

Electrical stimulation : an analog to LED flash

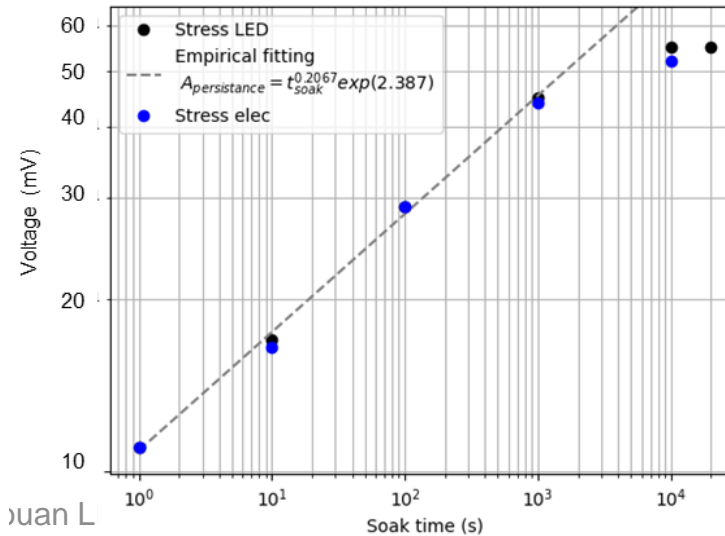
- Abrupt voltage change with soak time
- Accounts well for stress **below saturation**



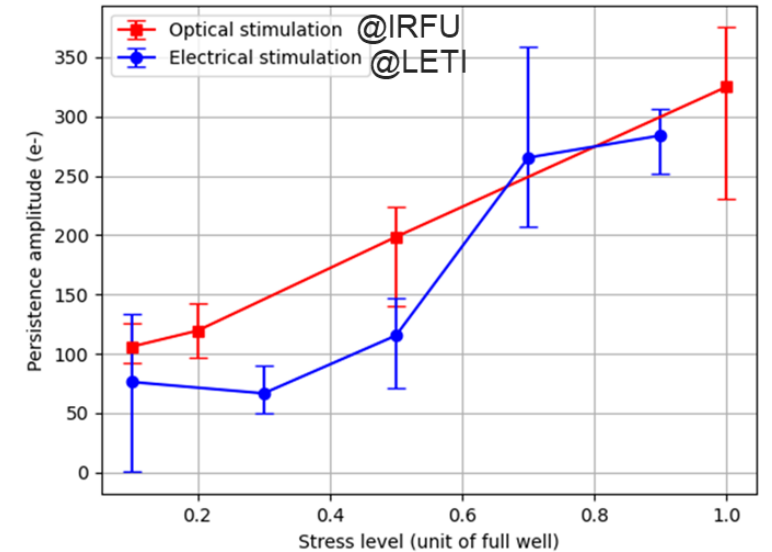
Persistence time constant



Persistence amplitude



Comparison of persistence level on the three best flavors of CH2404



Persistence as a tool to evaluate a technology performance

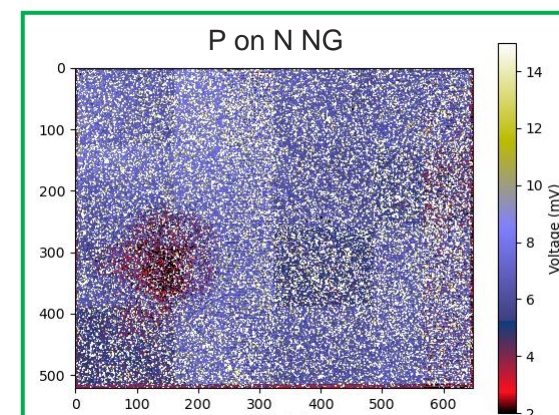
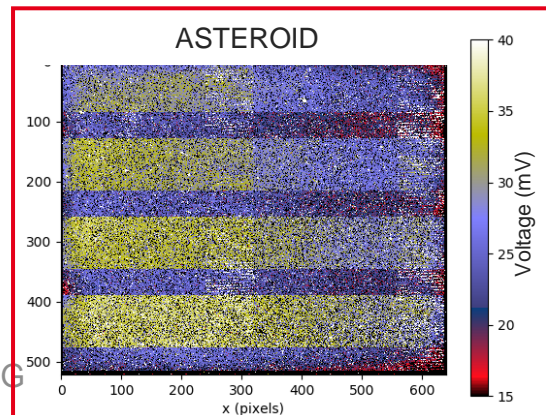
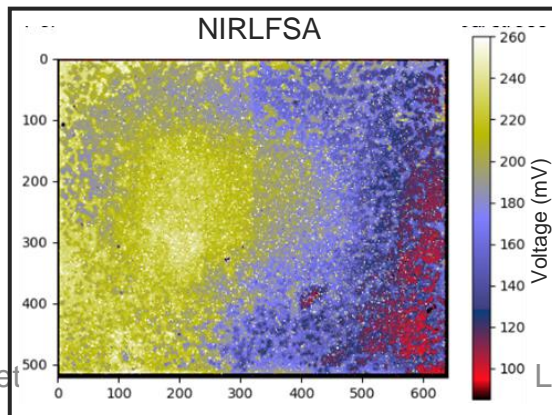
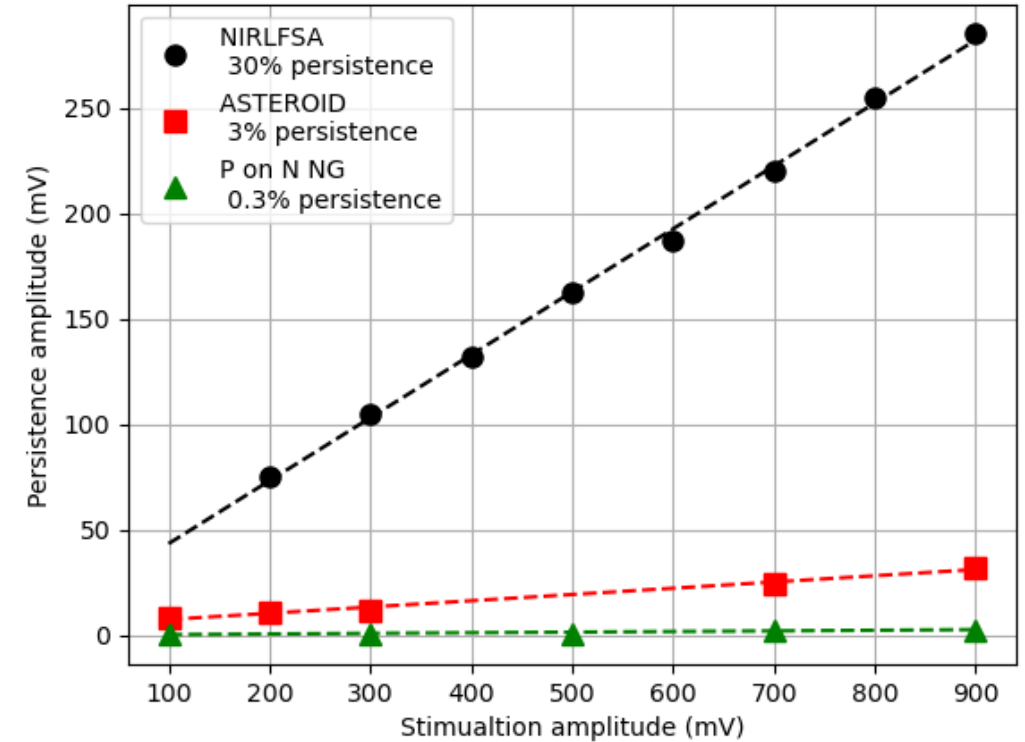
□ Electrical stress persistence: ⚡

- Easier to carry out
- 'Infinite' soak time maximizes persistence emission

□ Comparison on succeeding in-house technologies

- Similar equipment and test protocol
- Persistence can be mitigated with material quality & diode fabrication improvement

Persistence amplitude and slope
Electrical stimulation @ 100 K



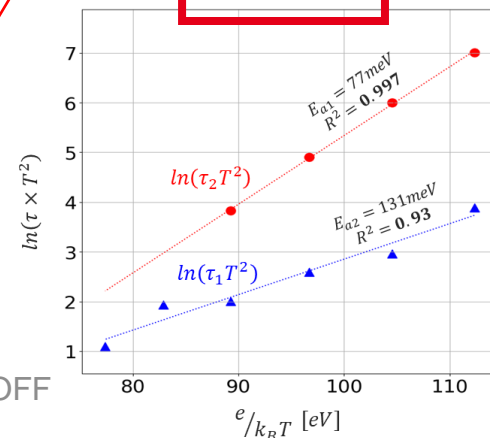
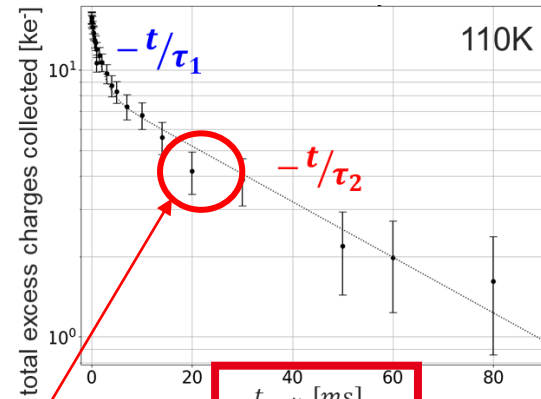
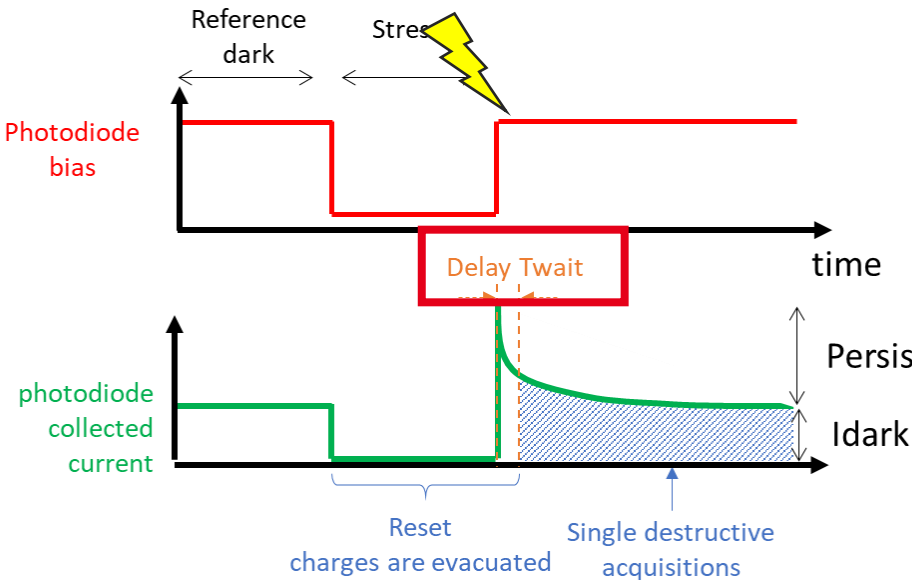
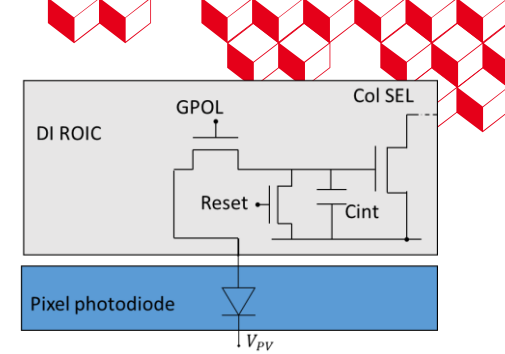
Persistence as trap analysis tool

❑ Electrical persistence adapted on Direct Injection (defense application oriented ROIC)

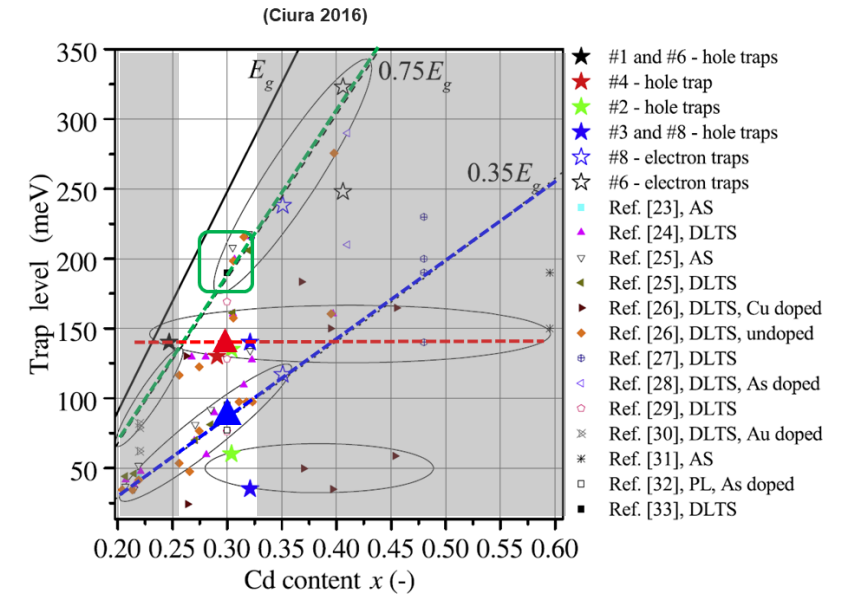
-> Current transient integrated on a fixed C_{int}

-> Destructive readout mode : A **delay twait** inserted after the stress to reconstruct trap decay dynamic.

Performed on MCT SWIR, MWIR, P/N, N/P and T2SL arrays... Should also work on CTIA ROIC



Coherent trap properties estimation with littérature on MCT MWIR !



H. Rousset & al, Journal of Electronic Materials, 2025



Persistence on test chip

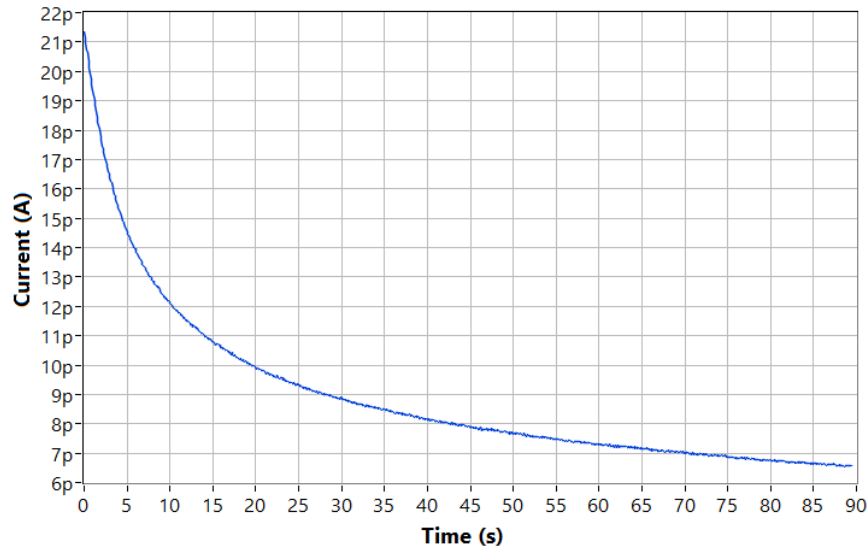


- A setup for persistence diagnostic with test chips

- On FPA → final product but **costly** and reluctance to perform **post process treatments**
- On test arrays → how to measure **low currents** with on-the-self amplifiers?

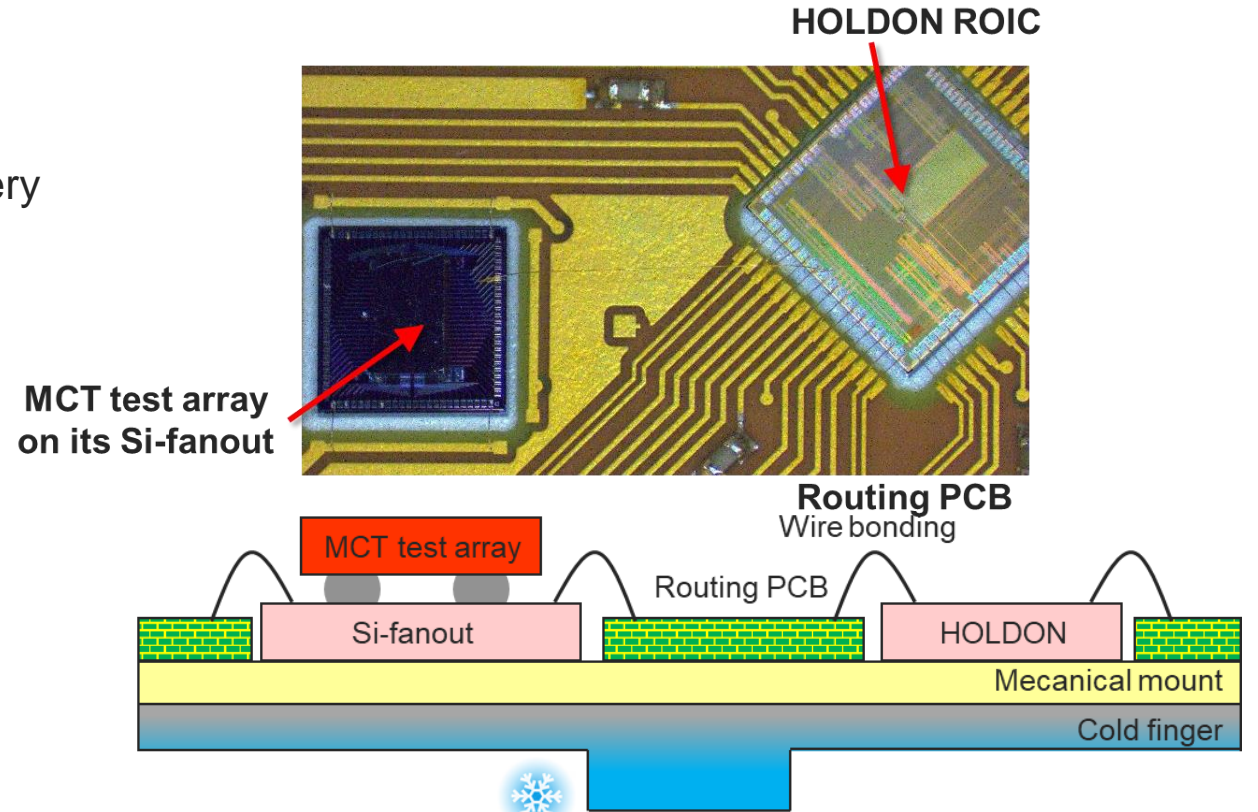
- First results: electrical remanence test on SWIR test array ($\lambda_c = 2.1\mu m$)

- Both electrical & optical stimulus possible
- Large memory depth : adaptable sampling for fast & very long acquisition



- Solution: coupling test array to **CTIA ROIC**

- Single diode **CTIA input ROIC**
- High operating frequency (up to 300MHz)
- Non destructive readout (fast sampling & observation up to several hours)
- Fully reconfigurable (during acquisition) 4 gains CTIA





3 ■ 4 Irradiation testing

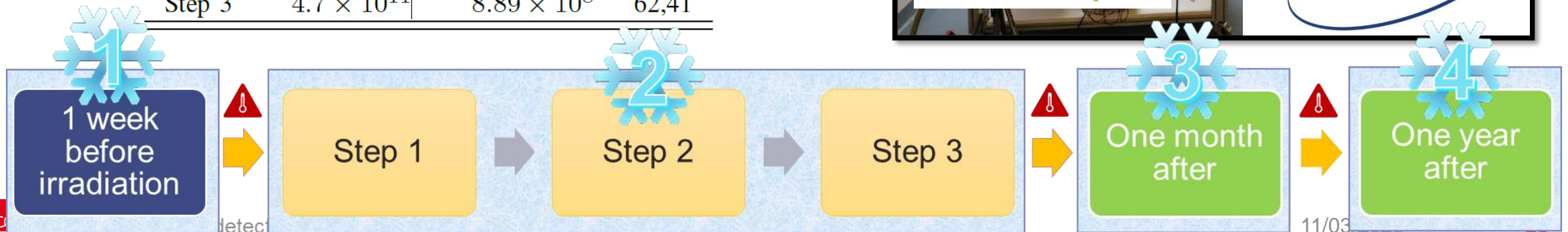
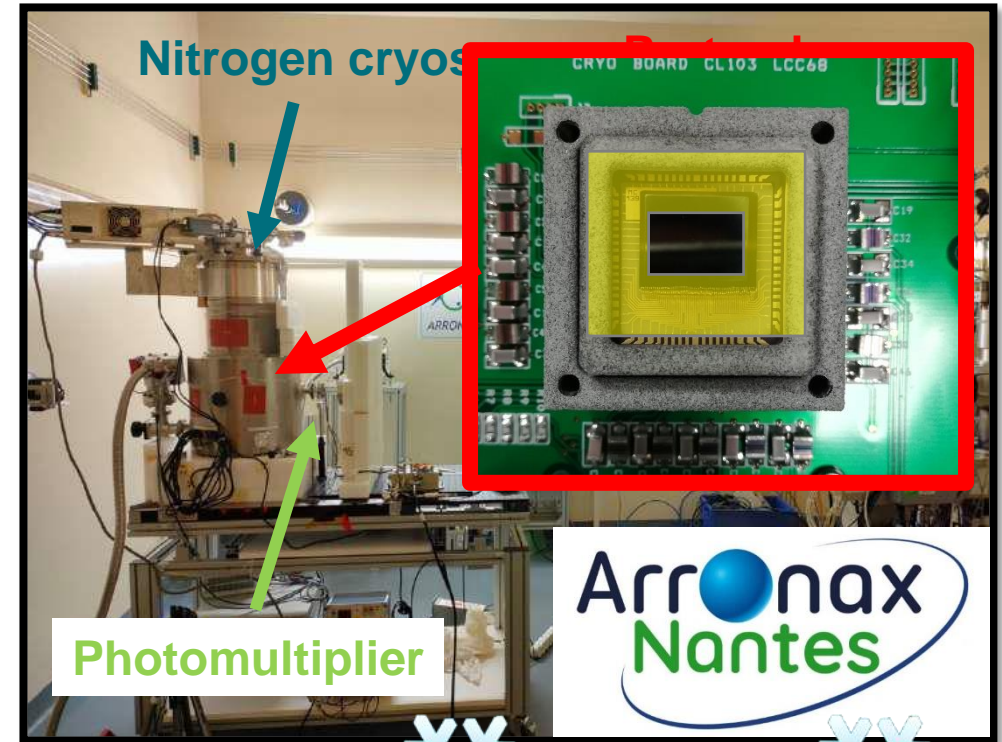
Irradiation testing

Why ? Technology evaluation, defect formation after irradiation stressing

→ Irrad are performed at much higher dose than EOL !

- Proton/neutron/ γ_{ray} irradi on tactical MWIR N/P (S. Dinand)
- Dark current & RTS on LWIR & VLWIR P/N (T. Friess & A. Claret)
- **Dark current degradation on SWIR P/N Source-Follower detector** (T. Friess & T. Pichon)

	Cumulative fluence (<i>proton/cm²</i>)	TNID MeV/g (HgCdTe)	TID krad (Si)
Step 1	1.6×10^{10}	3.03×10^7	2.12
Step 2	1.5×10^{11}	2.84×10^8	19,91
Step 3	4.7×10^{11}	8.89×10^8	62,41



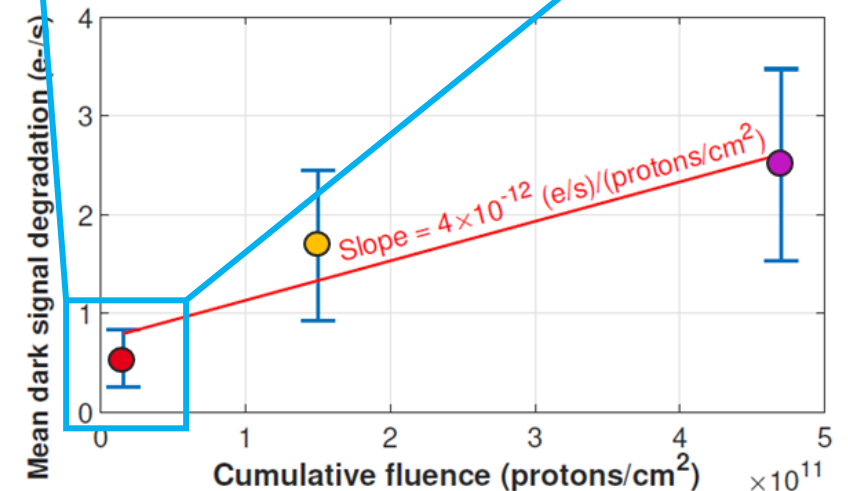
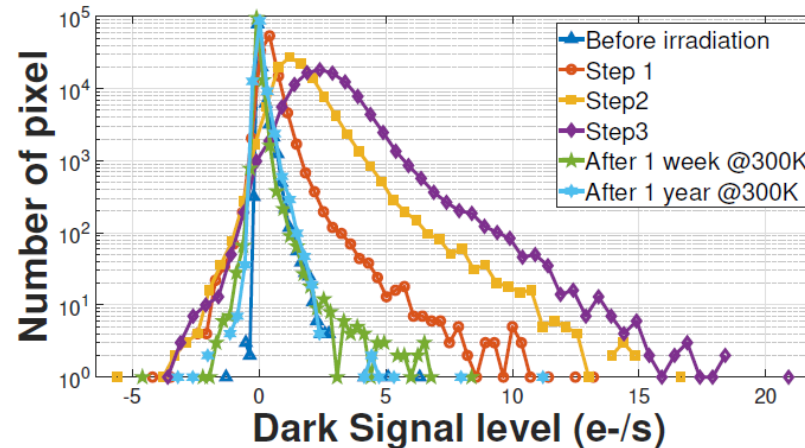
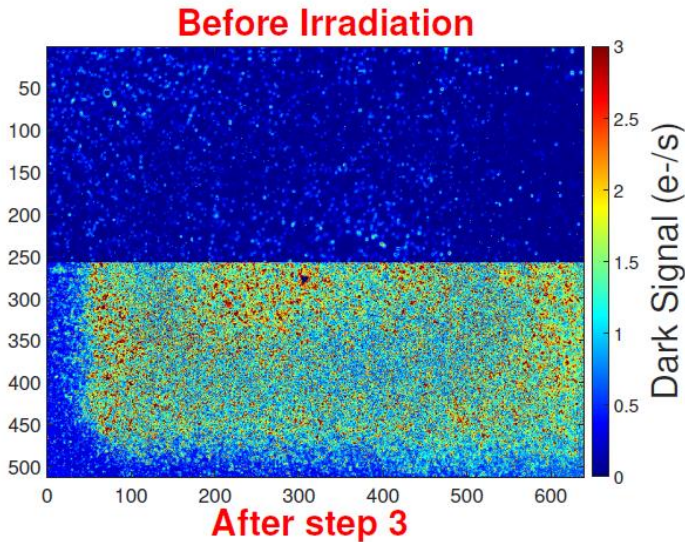
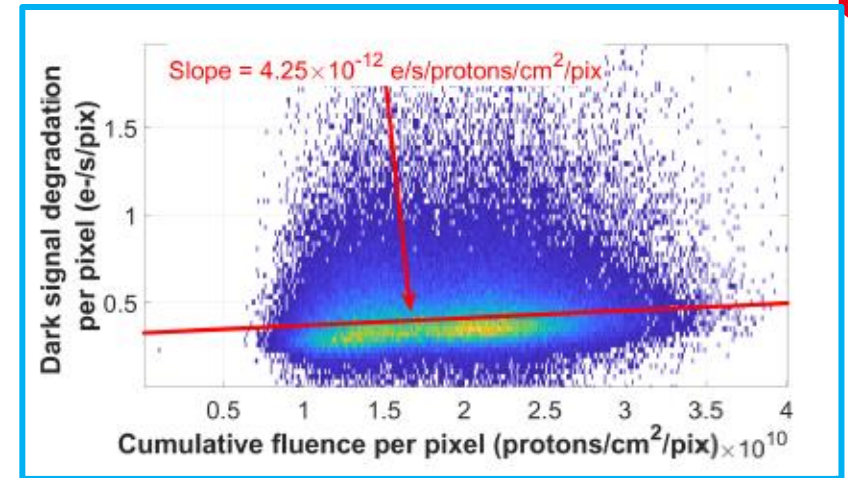
Irradiation testing

- ❑ Dark current increase after irradiation from 0,05 e-/s to > 2e-/s
- ❑ Linear dark current degradation = additive defect formation
 - Also valid for low dose irradiation

$$1,8 \times 10^{-6} e - /s/pix/proton$$

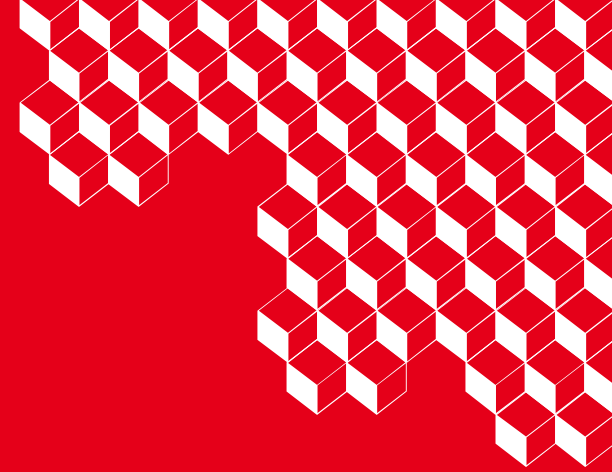
$$3 \times 10^{-10} fA/pix/proton$$

- ❑ Recovery of the initial performance after a thermal cycle at ambient temperature
 - Thermal reconfiguration of defects ?





leti



**Thank
you**

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